

Atty. Dkt. No.	M#	Client Ref.
	306525	P-1586.010-US

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Applicant:	Joeri LOF <i>et al.</i>
Appln. No.:	Unknown
Filing Date:	November 12, 2003
Examiner:	Unknown
Group Art Unit:	Unknown

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Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
	AR 3,573,975	04/1971	Dhaka <i>et al.</i>	117	212	
	BR 3,648,587	03/1972	Stevens	95	44	
	CR 4,346,164	08/1982	Tabarelli <i>et al.</i>	430	311	
	DR 4,396,705	08/1983	Akeyama <i>et al.</i>	430	326	
	ER 4,480,910	11/1984	Takanashi <i>et al.</i>	355	30	
	FR 4,509,852	04/1985	Tabarelli <i>et al.</i>	355	30	
	GR 5,040,020	08/1991	Rauschenbach <i>et al.</i>	355	53	
	HR 5,121,256	06/1992	Corle <i>et al.</i>	359	664	
	IR 5,610,683	03/1997	Takahashi	355	53	
	JR 5,715,039	02/1998	Fukuda <i>et al.</i>	355	53	
	KR 5,825,043	10/1998	Suwa	250	548	
	LR 5,900,354	05/1999	Batchelder	430	395	
	MR 6,191,429	02/2001	Suwa	250	548	
	NR 6,560,032	05/2003	Hatano	359	656	

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	Document Number	Date MM/YYYY	Country	Inventor Name		English Abstract		Translation Readily Available	
						Enclosed	No	Enclose	No
	OR WO 99/49504	09/1999	PCT	Fukami <i>et al.</i>		X		X	
	PR EP 0023231	02/1981	Europe	Tabarelli <i>et al.</i>		X			
	QR EP 0418427	03/1991	Europe	Miyake		X		X	
	RR EP 1039511	09/2000	Europe	Murakimi <i>et al.</i>		X		X	
	SR DD 224448	07/1985	German	Hesse <i>et al.</i>			X		
	TR DD 242880	02/1987	German	Kuch			X		
	UR FR 2474708	07/1981	France	Letellier			X		
	VR JP 62-065326	03/1987	Japan	Moriuchi		X			
	WR JP 62-121417	06/1987	Japan	Nakazawa		X			
	XR JP 63-157419	06/1988	Japan	Nakasuji		X			

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YR	EP Search Report for EP 02257938 dated September 25, 2003			
ZR	M. Switkes <i>et al.</i> , "Immersion Lithography at 157 nm", MIT Lincoln Lab, Orlando 2001-1, December 17, 2001			
AAR	M. Switkes <i>et al.</i> , "Immersion Lithography at 157 nm", J. Vac. Sci. Technol. B., Vol. 19, No. 6, November/December 2001, pp. 2353-2356			
BBR	M. Switkes <i>et al.</i> , "Immersion Lithography: Optics for the 50 nm Node", 157 Anvers-1, September 4, 2002			

Examiner Date Considered:

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

FORM PTO-1449 (modified)
To: U.S. Department of Commerce
(PW FORM PAT-1449)
Patent and Trademark Office

Atty.
Dkt. No.

M#

Client Ref.

306781

P-0381.010-US

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Applicant: Joeri LOF *et al.*

Appln. No.: Unknown

Filing Date: November 12, 2003

Date: November 12, 2003

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of

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Examiner: Unknown

Group Art Unit: Unknown

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	CCR	6,603,130	08/2003	Bisschops <i>et al.</i>	250	492.1	
	DDR	6,633,365	10/2003	Suenaga	355	53	
	EER	2002/0163629	11/2002	Switkes <i>et al.</i>	355	53	
	FFR	2003/0123040	07/2003	Almogoy	355	69	
	GGR	2003/0174408	09/2003	Rostalski <i>et al.</i>	359	642	
	HHR						
	IIR						
	JJR						
	KKR						
	LLR						
	MMR						
	NNR						
	OOR						
	PPR						

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		Document Number	Date MM/YYYY	Country	Inventor Name		English Abstract		Translation Readily Available	
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	QQR	JP 04-305915	10/1992	Japan	Ozeki <i>et al.</i>		X			
	RRR	JP 04-305917	10/1992	Japan	Ozeki <i>et al.</i>		X			
	SSR	JP 06-124873	05/1994	Japan	Takahashi		X		X	
	TTR	JP 07-220990	08/1995	Japan	Fukuda <i>et al.</i>		X			
	UUR	JP 10-228661	08/1998	Japan	Kurokawa		X			
	VVR	JP 10-255319	09/1998	Japan	Suenaga <i>et al.</i>		X			
	WWR	JP 10-303114	11/1998	Japan	Suwa		X		X	
	XXR	JP 10-340846	12/1998	Japan	Kudo		X		X	
	YYR	JP 2001-091849	04/2001	Japan	Aizaki <i>et al.</i>		X			
	ZZR									

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	AAAR	B.J. Lin, "Drivers, Prospects and Challenges for Immersion Lithography", TSMC, Inc., September 2002				
	BBBR	B.J. Lin, "Proximity Printing Through Liquid", IBM Technical Disclosure Bulletin, Vol.20, No. 11B, April 1978, p. 4997				

Examiner

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CCC						
DDD						
EEE						

FOREIGN PATENT DOCUMENTS

OVERVIEW OF DOCUMENTS							Abstract		Readily Available	
		Document Number	Date MM/YYYY	Country	Inventor Name		Enclosed	No	Enclose	No
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HHH	B.J. Lin, "The Paths To Subhalf-Micrometer Optical Lithography", SPIE Vol. 922, Optical/Laser Microlithography (1988), pp. 256-269			
IIIR	G.W.W. Stevens, "Reduction of Waste Resulting from Mask Defects", Solid State Technology, August 1978, Vol.21 008, pp. 68-72			
JJJR	S. Owa et al., "Immersion Lithography; its potential performance and issues", SPIE Microlithography 2003, 5040-186, February 27, 2003			
KKK	S. Owa et al., "Advantage and Feasibility of Immersion Lithography", Proc. SPIE 5040 (2003)			
LLL	Nikon Precision Europe GmbH, "Investor Relations - Nikon's Real Solutions", May 15, 2003			
MMM	H. Kawata et al., "Optical Projection Lithography using Lenses with Numerical Apertures Greater than Unity", Microelectronic Engineering 9 (1989), pp. 31-36			
NNN	J.A. Hoffnagle et al., "Liquid Immersion Deep-Ultraviolet Interferometric Lithography", J. Vac. Sci. Technol. B., Vol. 17, No. 6, November/December 1999, pp. 3306-3309			
OOO	B.W. Smith <i>et al.</i> , "Immersion Optical Lithography at 193nm", FUTURE FAB International, Vol. 15, July 11, 2003			
PPP	H. Kawata et al., "Fabrication of 0.2µm Fine Patterns Using Optical Projection Lithography with an Oil Immersion Lens", Jpn. J. Appl. Phys. Vol. 31 (1992), pp. 4174-4177			
QQQ	G. Owen et al., "1/8µm Optical Lithography", J. Vac. Sci. Technol. B., Vol. 10, No. 6, November/December 1992, pp. 3032-3036			
RRR				
SSS				
TTT				
UUU				
VVV				
WWW				
XXX				
YYY				

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